Invitation & Agenda

MNE-2021 Turin BEAMeeting IN PRESENCE AND ON-LINE September 20, 2021

Time: September 20, 2021
Location: **Conference Room Madrid,**
Lingotto Convention and Exhibition Center Torino, Italy & Web via MS-TEAMS

Our BEAMeetings are focussed on E-Beam lithography, data-preparation, PEC, process correction, and lithography simulation. The meeting is a technical exchange platform for BEAMER users and those who are interested in BEAMER and other GenISys software. We have an excellent program this year with great customer presentations. Please see the attached Agenda for more details.

Face-to-face communication is always the most effective means of communication and if you have the possibility to be in Turin, join our BEAMeeting in person and have a chance discussing and sharing ideas with other attendees.

The BEAMeeting is free of charge, it will be held at the Conference Room Madrid, Lingotto Convention and Exhibition Center Torino and on-line via MS-Teams.

In the afternoon there will be the Maskless Laser Lithography and Direct Writing for Nano- and Microfabrication – Technical Workshop & Discussion organized by Heidelberg Instruments (HIMT), micro resist technology, Multiphoton Optics and GenISys.

REGISTRATION - On Site and On-Line

- **REGISTRATION for On Site**
- **REGISTRATION for On-LINE**

See you in Turin-Italy or on-line via MS-Teams – The GenISys Team

<table>
<tr><td colspan="3">BEAMeeting E-Beam Workshop
Technical Workshop & Discussion</td></tr>
<tr><td colspan="3">Date: Monday, Sept. 20th, 2021 - Time: 09:00 – 12:30 pm
Turin – Italy & Online</td></tr>
<tr><td colspan="3">Agenda</td></tr>
<tr><td>Mike Butler
GenISys</td><td>Welcome & Introduction</td><td>9:00</td></tr>
<tr><td>Nezih Ünal
GenISys</td><td>GenISys Update</td><td>9:10</td></tr>
<tr><td>Kimihiko Kato
AIST
Tsukuba, Japan</td><td>Electron Beam Lithography for Future Highly-Integrated Si Quantum Bits</td><td>9:30</td></tr>
<tr><td>Ulrich Hofmann
GenISys</td><td>ProSEM Metrology Software
New feature and Enhancements</td><td>9:50</td></tr>
<tr><td>Irina Harder
MPI Erlangen</td><td>Can BEAMER help with High Resolution Laser Lithography exposure?</td><td>10:10</td></tr>
<tr><td></td><td>Coffee Break</td><td>10:30</td></tr>
<tr><td>Sylvia Diewald
KIT
Karlsruhe, Germany</td><td>Asymmetric Undercuts in bi-layer systems, 3D-PEC, Simulation</td><td>10:50</td></tr>
<tr><td>Aditya Reddy
GenISys</td><td>Valuable Modules often overlooked
(Filter / Extract / Replace)</td><td>11:10</td></tr>
<tr><td>Dr. Olaf Brox
FBH-Berlin</td><td>E-beam DataPrep for AlGaAs Diode Laser Gratings and InP HBTs</td><td>11.30</td></tr>
<tr><td>Thomas Michels
GenISys</td><td>Update in BEAMER /TRACER /LAB
Roadmap, Wishes & Discussion</td><td>11.50</td></tr>
<tr><td></td><td>Lunch</td><td>12:30</td></tr>
<tr><td>Afternoon:</td><td>Maskless Laser Lithography and Direct Writing for Nano- and Microfabrication – Technical Workshop & Discussion</td><td></td></tr>
<tr><td></td><td>Move to MNE - Welcome Reception</td><td>17:00</td></tr>
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